

ABSTRACT

A method for depositing a high quality metal oxide film onto a substrate of a plasma display panel is provided. At a process for forming protective layer (8) of MgO film which is a metal oxide film, the film is formed in such a manner
5 that partial pressure of oxygen gas or the like in evaporation room (21) which is a deposition room is within a certain range. Using this method, deposition is performed with an atmosphere in evaporation room (21) constant, so that physical properties of a film can be stabilized. As a result, a plasma display panel which can display high quality images can be manufactured.